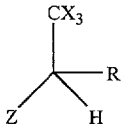
What is claimed is:

1. A photoresist composition comprising a polymeric binder, a photoactive component, a photoresist strip enhancer and optionally a cross-linking agent, wherein the photoresist strip enhancer is non-polymerizable with the polymeric binder, optional cross-linking agent or both and has the formula



wherein each X is independently chlorine, bromine, fluorine or iodine; Z = cyano, aryl, substituted aryl, C(Y)-R^1, C≡C-R^2 and C(R^3)=CR^4R^5; Y = oxygen or sulfur; R = Z, hydrogen, (C_1-C_4)alkyl, (C_1-C_4)alkoxy, substituted (C_1-C_4)alkyl, substituted (C_1-C_4)alkoxy; R^1 = (C_1-C_8)alkyl, (C_1-C_8)alkoxy, substituted (C_1-C_8)alkyl, substituted (C_1-C_8)alkoxy, aryl or substituted aryl; R^2 = hydrogen, (C_1-C_8)alkyl, substituted (C_1-C_8)alkyl, aryl or substituted aryl; and R^3, R^4 and R^5 are independently selected from hydrogen, halogen or R^1.

2. The composition of claim 1 wherein at least one of Z and R is aryl or alkenyl.

3. The composition of claim 1 wherein R is phenyl or alkenyl and Z is aryl, -C(Y)-R^1 or -O-C(Y)-R^1.

4. The composition of claim 1 wherein the photoresist strip enhancer is selected from alpha-trichloromethyl benzyl acetate, alpha-tribromomethyl benzyl acetate, alpha-triiodomethyl benzyl acetate, trichloromethyl allyl acetate, tribromomethyl allyl acetate, alpha-trichloromethyl benzyl propionate, alpha-tribromomethyl benzyl propionate, alpha-triiodomethyl benzyl propionate, trichloromethyl allyl propionate, tribromomethyl allyl propionate, alpha-trichloromethyl benzyl benzoate, alpha-tribromomethyl benzyl benzoate, alpha-triiodomethyl benzyl benzoate, trichloromethyl allyl benzoate, tribromomethyl allyl benzoate or alpha-bromodichloromethyl benzyl acetate.

5. The composition of claim 1 wherein the photoactive component is selected from 9-phenylacridine, n-phenylglycine, benzophenone, N, N'-tetramethyl-4, 4'-diaminobenzophenone, N,N'-tetraethyl-4,4'-diaminobenzophenone, 4-methoxy-4'-dimethylaminobenzophenone, 3,3'-dimethyl-4-methoxybenzophenone, p,p'-

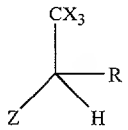
bis(dimethylamino)benzophenone, p,p'-bis(diethylamino)-benzophenone, anthraquinone, 2-ethylanthraquinone, naphthaquinone, phenanthraquinone, benzoin, benzoinmethylether, benzoinethylether, benzoinisopropylether, benzoin-n-butylether, benzoin-phenylether, methylbenzoin, ethybenzoin, dibenzyl, benzyldiphenyldisulfide, benzyldimethylketal, 1,7-bis(9-acridinyl)heptane, 2-chlorothioxanthone, 2-methylthioxanthone, 2,4-diethylthioxanthone, 2,4-dimethylthioxanthone, 2-isopropylthioxanthone, 1,1-dichloroacetophenone, p-t-butyldichloro-acetophenone, 2,2-diethoxyacetophenone, 2,2-dimethoxy-2-phenylacetophenone, 2,2-dichloro-4-phenoxyacetophenone, 2-(o-chlorophenyl)-4,5-diphenylimidazole dimer, 2-(o-chlorophenyl)-4,5-di(m-methoxyphenyl imidazole dimer, 2-(o-fluorophenyl)-4,5-diphenylimidazole dimer, 2-(o-methoxyphenyl)-4,5-diphenylimidazole dimer, 2-(p-methoxyphenyl)-4,5-diphenylimidazole dimer, 2,4-di(p-methoxyphenyl)-5-phenylimidazole dimer, 2-(2,4-dimethoxyphenyl)-4,5-diphenylimidazole dimer or 2-(p-methylmercaptophenyl)-4,5-diphenylimidazole dimer.

6. The composition of claim 1 wherein the polymeric binder comprises sufficient acid functionality to render said photoimageable composition developable in alkaline aqueous solution.

7. The composition of claim 6 wherein the polymeric binder has an acid number of from about 50 to about 250.

8. The composition of claim 1 wherein the photoresist strip enhancer is present in an amount up to 10 %wt.

9. A method of enhancing the removal of a photoresist composition from a substrate comprising the step of combining a photoresist strip enhancer with a photoresist composition comprising polymeric binder, a photoactive component and optionally a cross-linking agent, wherein the photoresist strip enhancer is non-polymerizable with the polymeric binder, optional cross-linking agent or both and has the formula



wherein each X is independently chlorine, bromine, fluorine or iodine; Z = cyano, aryl, substituted aryl, C(Y)-R^1, C≡C-R^2 and C(R^3)=CR^4R^5; Y = oxygen or sulfur; R = Z, hydrogen, (C_1-C_4)alkyl, (C_1-C_4)alkoxy, substituted (C_1-C_4)alkyl, substituted (C_1-C_4)alkoxy; R^1 = (C_1-

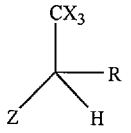
C_8)alkyl, (C_1-C_8)alkoxy, substituted (C_1-C_8)alkyl, substituted (C_1-C_8)alkoxy, aryl or substituted aryl; R^2 = hydrogen, (C_1-C_8)alkyl, substituted (C_1-C_8)alkyl, aryl or substituted aryl; and R^3, R^4 and R^5 are independently selected from hydrogen, halogen or R^1.

10. The method of claim 9 wherein at least one of Z and R is aryl or alkenyl.

11. The method of claim 9 wherein is phenyl or alkenyl and Z is aryl, -C(Y)-R^1 or -O-C(Y)-R^1.

12. The method of claim 11 wherein the photoresist strip enhancer is selected from alpha-trichloromethyl benzyl acetate, alpha-tribromomethyl benzyl acetate, alpha-triiodomethyl benzyl acetate, trichloromethyl allyl acetate, tribromomethyl allyl acetate, alpha-trichloromethyl benzyl propionate, alpha-tribromomethyl benzyl propionate, alpha-triiodomethyl benzyl propionate, trichloromethyl allyl propionate, tribromomethyl allyl propionate, alpha-trichloromethyl benzyl benzoate, alpha-tribromomethyl benzyl benzoate, alpha-triiodomethyl benzyl benzoate, trichloromethyl allyl benzoate, tribromomethyl allyl benzoate or alpha-bromodichloromethyl benzyl acetate.

13. A method of manufacturing a printed wiring board comprising the steps of: a) disposing on a printed wiring board substrate a photoresist composition comprising a polymeric binder, a photoactive component, a photoresist strip enhancer and optionally a cross-linking agent, wherein the organic acid is non-polymerizable with the polymeric binder and optional cross-linking agent and has the formula



wherein each X is independently chlorine, bromine, fluorine or iodine; Z = cyano, aryl, substituted aryl, C(Y)-R^1, C≡C-R^2 and C(R^3)=CR^4R^5; Y = oxygen or sulfur; R = Z, hydrogen, (C_1-C_4)alkyl, (C_1-C_4)alkoxy, substituted (C_1-C_4)alkyl, substituted (C_1-C_4)alkoxy; R^1 = (C_1-C_8)alkyl, (C_1-C_8)alkoxy, substituted (C_1-C_8)alkyl, substituted (C_1-C_8)alkoxy, aryl or substituted aryl; R^2 = hydrogen, (C_1-C_8)alkyl, substituted (C_1-C_8)alkyl, aryl or substituted aryl; and R^3, R^4 and R^5 are independently selected from hydrogen, halogen or R^1; b) imaging the photoresist; and c) developing the photoresist.

14. The method of claim 13 wherein at least one of Z and R is aryl or alkenyl.

15. The method of claim 14 wherein R is phenyl or alkenyl and Z is aryl, -C(Y)-R^1 or -O-C(Y)-R^1.

16. A method of enhancing the removal of a photoresist composition from a substrate comprising the step of combining a curing agent having a net acrylate functionality of about 2 or greater with a photoresist composition including polymeric binder and photoactive component.

17. The method of claim 16 wherein the curing agent comprises one or more acrylate cross-linking agents and one or more non-cross-linkable acrylate monomers.

18. The method of claim 16 wherein the curing agent comprises a triacrylate cross-linking agent and a non-cross-linkable acrylate monomer.

19. The method of claim 18 wherein the ratio of triacrylate cross-linking agent and non-cross-linkable acrylate monomer is about 1:1 by weight.

20. The method of claim 16 wherein the curing agent is free of methacrylate functionality.